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Author: Eun Kil Park Sung Min Kim Jaeyeong Heo Hyeong

Joon Kim

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Electrical Evaluation of Crack Generation in SiN_x and SiO_xN_y Thin-Film Encapsulation Layers for OLED Displays

Eun Kil Park^{a,b}, Sung Min Kim^a, Jaeyeong Heo^{c*} jheo@jnu.ac.kr, Hyeong Joon Kim^{a*} thinfilm@snu.ac.kr

^aDepartment of Materials Science and Engineering, Seoul National University, Seoul 151-744, Republic of Korea

^bDisplay Research Center, Samsung Display Co. Ltd., Yongin-City, Gyeonggi-Do 446-711, Republic of Korea

^cDepartment of Materials Science and Engineering, and the Optoelectronics Convergence Research Center, Chonnam National University, Gwangju 500-757, Republic of Korea

^{*}Corresponding authors.

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